## 研究论文

## UV-B辐射增强对两种不同抗性水稻叶片光合生理及超显微结构的影响 吴杏春 $^{1,2}$ , 林文雄 $^{2,*}$ , 黄忠良 $^{1}$

- 1. 中国科学院华南植物园,广州510000
- 2.福建农林大学生命科学学院,福州350002

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在UV-B辐射增强条件下,研究了两个不同水稻品种叶片光合作用系统的变化。结果表明: (1) UV-B辐 射胁迫使两个水稻品种叶片总叶绿素含量,叶绿素a与叶绿素b (Chla/Chlb) 比值下降,叶绿素a荧光诱导动力学参数 改变,光系统 II 活性受抑制,光合作用效率降低,其中Dular受抑制的程度较Lemont大。(2) 利用扫描电镜(SE M)和透射电镜(TEM)进一步研究表明,UV-B辐射胁迫使水稻叶片气孔器受破坏,叶绿体结构变形,基粒片 层排列稀疏紊乱,两个供试品种结构上受破坏的程度与它们光合生理受抑制的程度一致。(3)叶片边缘受破坏的 程度较主脉两侧轻,这可能与硅质乳突密度较大有关。(4)两个供试品种叶片表面主脉两侧的硅质乳突数量及其 受UV-B辐射影响的特性存在明显的差异,Lemont叶表面的乳突分布密度较大,且在UV-B辐射胁迫下有增加的 趋势,而Dular则相反。这说明硅质体的累积特性可能是水稻对UV-B辐射胁迫的适应机制之一。

关键词 光合作用系统; UV-B辐射; 水稻; 超显微结构

分类号 Q142, Q945, S314

Influence of enhanced ultraviolet-B radiation on photosy nthetic physiologies and ultrastructure of leaves in two d ifferent resistivity rice cultivars

WU Xi ng-Chun<sup>1, 2</sup>, LIN Wen-Xi ong<sup>2, \*</sup>, HUANG Zhong-Li ang<sup>1</sup>

1 South China Institute of Botany, Guangzhou 510000, China 2 School of Life Sciences, Fujian Agriculture and Forestry University, Fu 服务与反馈 zhou 350002, China

**Abstract** Depletion of stratospheric ozone (O3) caused by anthropogenic chlorofluorocarbons h as increased the amount of ultraviolet radiation, especially ultraviolet-B (280-320,UV-B) radiatio n reaching the Earth's surface. For every percentage decreases in stratospheric ozone, the amoun t of biologically effective UV-B radiation (UV-BBE) is predicated to increase by approximately d ouble that percentage. Enhanced UV-B radiation causes damage to the growing development an d physiobiochemical processes of plants. e.g. photosynthesis, which would induce the change o f morphological characteristics and alter normal metabolic processes.

This study was conducted to determine the effect of UV-B radiation on the photosynthetic physiol ogy and the ultrastructure of leaves in rice (Oryza sativa L.) . Three-leaf-aged seedlings of rice L emont (tolerant) and Dular (sensitive) were subjected to UV-B radiation 18.6kJ m<sup>-2</sup> d<sup>-1</sup> for treat ment in a network for 3 weeks, and natural light for control. Under 3-weeks of UV-B treatmen t, photosynthetic pigment, fluorescence induction kinetics parameters of chlorophyll a, photosynth etic efficiency, ultrastructure of leaf surface and mesophyll were investigated. The results showe d as follows: (1) UV-B radiation stress significantly decreased chlorophyll content, and the ratio o f chlorophyll a to chlorophyll b (Chla/Chlb), changed fluorescence induction kinetics parameters o f chlorophyll a, and in turn reduced photosynthetic efficiency. The tested rice cultivar, Dular, was i nhibited more seriously than Lemont. (2) Further studies with transmission electron microscopi c (TEM) observation and scanning electron microscope (SEM) observation, revealed that the sto matal apparatus was damaged, the chloroplast structure was distorted, the arrangement in the lam

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吴杏春

林文雄

黄忠良

ellae of the grana and stroma was loose and disordered. The effect of UV-B radiation stress on the ultrastructure of leaves in the two rice cultivars tested was consistent with their changes in photo synthetic physiology. (3)The adaxial surface was damaged more seriously than the abaxial surface e in the two rice cultivars. This might contribute to its higher density of silicic papillae. (4) The amount of silicic papillae on the adaxial surface in the two rice cultivars and their responses to UV-B radiation stress were significantly different, i.e. the amount of papilla in Lemont was higher than Dular, and was elevated by UV-B radiation. The reverse was true in the case of Dular. The findings suggested that the characteristics of silicic cumulation might be one of the mechanisms for rice adaptive to enhanced UV-B radiation stress.

**Key words** Oryza sativa L. photosynthetic physiology Ultraviolet-B radiation ultrastructure

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通讯作者 林文雄 wenxiong181@163.com